



## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

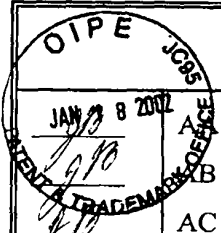
Electronic Version v18  
Stylesheet Version v18.0

<b>Title of Invention</b>	Inspection System By Charged Particle Bean And Method Of Manufacturing Devices Using The System																
Application Number: 09/891611 Confirmation Number: 8874 First Named Applicant: Mamoru Makasuji Attorney Docket Number: 010817 Art Unit: 2881 Examiner: Jack I Berman Search string: ( 5578821 ).pn.																	
<b>US Patent Documents</b>  Note: Applicant is not required to submit a paper copy of cited US Patent Documents																	
<table border="1"><thead><tr><th>Init</th><th>Cite.No.</th><th>Patent No.</th><th>Date</th><th>Patentee</th><th>Kind</th><th>Class</th><th>Subclass</th></tr></thead><tbody><tr><td><i>1C</i></td><td>1</td><td>5578821</td><td>1996-11-26</td><td>Meisberger et al</td><td></td><td>250</td><td>310</td></tr></tbody></table>		Init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass	<i>1C</i>	1	5578821	1996-11-26	Meisberger et al		250	310
Init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass										
<i>1C</i>	1	5578821	1996-11-26	Meisberger et al		250	310										
<b>Signature</b>																	
<table border="1"><thead><tr><th>Examiner Name</th><th>Date</th></tr></thead><tbody><tr><td><i>Jack I Berman</i></td><td><i>10/22/03</i></td></tr></tbody></table>		Examiner Name	Date	<i>Jack I Berman</i>	<i>10/22/03</i>												
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INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. 010817	Serial No. 09/891,611
	Applicant: Mamoru NAKASUJI et al.	
	Filing Date: June 27, 2001	Group Art Unit:

**FOREIGN PATENT DOCUMENTS**

	Document No.	Date	Country	Translation (Yes or No)
	52-115161 ✓	09/27/77	JAPAN	ABSTRACT
	52-117567 ✓	10/03/77	JAPAN	ABSTRACT
	57-072326 ✓	05/06/82	JAPAN	ABSTRACT
	57-125871 ✓	08/05/82	JAPAN	ABSTRACT
	60-000741 ✓	01/05/85	JAPAN	ABSTRACT
	62-195838 ✓	08/28/87	JAPAN	ABSTRACT
	03-022339 ✓	01/30/91	JAPAN	ABSTRACT
	03-053439 ✓	03/07/91	JAPAN	ABSTRACT
	03-102814 ✓	04/30/91	JAPAN	ABSTRACT
	03-266350 ✓	11/27/91	JAPAN	ABSTRACT
	03-276548 ✓	12/06/91	JAPAN	ABSTRACT
	04-266350 ✓	09/22/92	JAPAN	ABSTRACT
	05-063261 ✓	03/12/93	JAPAN	ABSTRACT
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	11-132975 ✓	05/21/99	JAPAN	ABSTRACT
	2000-090868 ✓	03/31/00	JAPAN	ABSTRACT

Examiner <i>Jack Berman</i>	Date Considered <i>10/22/03</i>
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<b>INFORMATION DISCLOSURE CITATION PTO-1449</b>	Atty. Docket No. 010817	Serial No. 09/891,611
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Examiner Initial	Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
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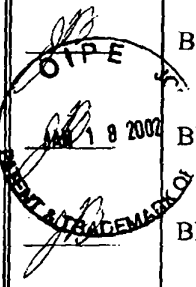
### OTHER DOCUMENTS

JP	BH	Low Voltage and high speed operating electrostatic wafer chuck using sputtered tantalum oxide membrane, Mamoru Nakasuji et al., J. Vac. Sci. Technol. A 12(5), Sep/Oct 1994, American Vacuum Society pp. 2834-2839.
JP	BI	High -Emittance and Low-Brightness Electron Gun for Reducing-Image Projection System: Computer Simulation, Mamoru Nakasuji et al., Jpn. J. Appl. Phys. Vol. 36 (1997) pp.2404-2408.
JP	BJ	H. Hayashi, et al., LSI Testing Symposium 1998, Minutes of the meeting, P160 (1998) (partial translation)
Examiner <i>Jack Berman</i>		Date Considered <i>10/22/03</i>

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<div style="text-align: center;">  </div>	BK ✓	Multi-Beam Concepts for Nanometer Devices, B. Lischke et al., Japanese Journal of Applied Physics, Vol. 28, No.10, October 1989, pp. 2058-2064. ✓
	BL ✓	An electron-beam inspecting system for x-ray mask production, P. Sandland et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec. 1991, American Vacuum Society, pp.3005-3009. ✓
	BM ✓	Requirements and performance of an electron-beam column designed for x-ray mask inspection, W.D. Meisburger et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec 1991, American Vacuum Society, pp.3010-3014.
	BN ✓	Table 5-1 Work Function in Metals page 116.

Examiner <i>Jack Berman</i>	Date Considered <i>10/22/07</i>
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